IN THE CLAIMS

Please amend the claims as follows:

- (Currently Amended) A rendering system comprising:
- a force modeler that is configured to model for modeling forces that are applied to a glyph in dependence upon a placement of the glyph, and
- a glyph positioner, operably coupled to the force modeler, that is configured to selection selecting a preferred placement of the glyph, based on the forces that are applied to the glyph at the preferred placement,
- wherein the force modeler determines the forces that are applied to

 the glyph based on at least one of a force-density model, a spring

 model, and a gravity well model.
 - 2. (Currently Amended) The rendering system of as claimed in claim 1, wherein said rendering system further including comprises:
 - a glyph scaler that is configured to provide for providing the glyph to the glyph positioner, based on a glyph description.
 - 3. (Currently Amended) The rendering system of as claimed in claim 1, wherein said rendering system further including comprises:

at least one of a display device and a print device that is configured to render for rendering the glyph at the preferred placement.

4. (Currently Amended) The rendering system of as claimed in claim 1, wherein:

the force modeler is configured to determined the forces that are applied to the glyph based upon an amount of coverage of a set of pixels of an array of pixels.

5. (Currently Amended) The rendering system of as claimed in claim 4, wherein:

the set of pixels comprises pixels that are partially covered by the glyph.

6. (Currently Amended) The rendering system of as claimed in claim 4, wherein:

the force modeler is—further configured to

determinedetermines the forces that are applied to the glyph based
on a preferred spacing of the glyph relative to an adjacent glyph.

7. (Currently Amended) The rendering system of as claimed in claim 1, wherein:

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the force modeler is configured to determine further determines the forces that are applied to the glyph based on a preferred spacing of the glyph relative to an adjacent glyph.

- 8. (Cancelled).
- 9. (Currently Amended) The rendering system of as claimed in claim 1, wherein:

the force modeler is configured to determine further determines the forces that are applied to the glyph, based on a coverage of one or more pixels by the glyph, so as to effect a change of the coverage of the one or more pixels by the glyph.

10. (Currently Amended) A method of rendering a glyph to an array of pixels, the method comprising the steps of:

modeling forces that are applied to the glyph in dependence upon a placement of the glyph, -; and

selecting a preferred placement of the glyph, based on the forces that are applied to the glyph at the preferred placement, wherein the modeling step determines the forces that are applied to the glyph based on at least one of a force-density model, a spring model, and a gravity well model.

- 11. (Currently Amended) The method of as claimed in claim 10, wherein said method further including comprises the step of:
 scaling the glyph, based on a description of the glyph.
- 12. (Currently Amended) The method of—as claimed in claim 10, wherein said method further including comprises the step of:

rendering the glyph at the preferred placement on at least one of: a display device and a printer device.

13. (Currently Amended) The method of as claimed in claim 10, wherein:

determining—said modeling step determines the forces that are applied to the glyph is based upon an amount of coverage of a set of pixels of the array of pixels.

14. (Currently Amended) The method of as claimed in claim 13, wherein:

the set of pixels comprises pixels that are partially covered by the glyph.

15. (Currently Amended) The method of-as claimed in claim 13, wherein:

determining said modeling step further determines the forces that are applied to the glyph is further based on a preferred spacing of the glyph relative to an adjacent glyph.

16. (Currently Amended) The method of as claimed in claim 10, wherein:

determining-said modeling step determines the forces that are applied to the glyph is based on a preferred spacing of the glyph relative to an adjacent glyph.

- 17. (Cancelled).
- (Currently Amended) The method of as claimed in claim 10, 18. wherein:

determining said modeling step determines the forces that are applied to the glyph is based on a coverage of one or more pixels by the glyph, so as to effect a change of the coverage of the one or more pixels by the glyph.